



# 제 29회 한국반도체학술대회

The 29th Korean Conference on Semiconductors

2022년 1월 24일(월)~ 26일(수) | 강원도 하이원 그랜드호텔(컨벤션타워)

2022년 1월 25일(화), 16:00-17:45

Room K (다이아몬드 I, 6층)

## F. Silicon and Group-IV Devices and Integration Technology 분과 [TK3-F] Advanced Process Technology

좌장: 김경록 교수(UNIST)

<p>TK3-F-1 16:00-16:30</p>	<p><b>Highly Reliable 28-nm Embedded Flash Process for High-density and High-speed Automotive Grade-1 (-40~150°C) Applications</b> Yong Kyu Lee, Jaehun Lee, HyunJin Shin, MyeongHee Oh, and Changmin Jeon <i>Foundry Business, Samsung Electronics Co., Ltd</i></p>
<p>TK3-F-2 16:30-16:45</p>	<p><b>Hybrid MIM Capacitor in 45-nm Embedded Flash Process for Touch IC</b> DongHwi Hwang, SoJeong Jeon, Hyunik Park, Jaehun Lee, Jongsung Woo, Kyongsik Yeom, Changmin Jeon, Youngho Kim, and Yong Kyu Lee <i>Foundry Business, Samsung Electronics Co., Ltd.</i></p>
<p>TK3-F-3 16:45-17:00</p>	<p><b>Dopant Activation of Ga implanted SiGe/SiGe:B by Nanosecond Laser Annealing</b> Kiseok Lee, Seunghyun Baik, Joosung Kang, Dongmin Yoon, So Young Kim, Hyerin Shin, Jin Woo Moon, Dongchan Suh, Heungsoo Park, and Dae-Hong Ko <i>Department of Materials Science and Engineering, Yonsei University</i></p>
<p>TK3-F-4 17:00-17:15</p>	<p><b>Effects of Nanosecond Laser Annealing on the Evolution of Microstructures and Strain Behaviors in the SiGe Epitaxial Films Grown on Nano-structured Si Wafer</b> Chunghee Jo<sup>1</sup>, Yongjoon Choi<sup>1</sup>, Dongmin Yoon<sup>1</sup>, So Young Kim<sup>1</sup>, Hyerin Shin<sup>1</sup>, Dong Chan Suh<sup>2</sup>, Heungsoo Park<sup>2</sup>, and Dae-Hong Ko<sup>1</sup> <sup>1</sup>Department of Material Science and Engineering, Yonsei University, <sup>2</sup>BIO-IT Micro Fab Center, Yonsei University</p>
<p>TK3-F-5 17:15-17:30</p>	<p><b>Process Simplification of Nanosheet FET with Doped Ultra-Thin Layer on Substrate</b> Khwang-Sun Lee and Jun-Young Park <i>Chungbuk National University</i></p>
<p>TK3-F-6 17:30-17:45</p>	<p><b>Approach for Ge-Rich SiGe Growth Using Ge Deposited by PVD Method</b> Unhyun Im and Sangwan Kim <i>Department of Electrical and Computer Engineering, Ajou University</i></p>